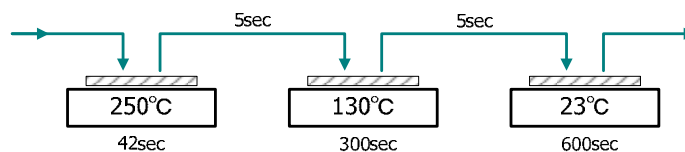
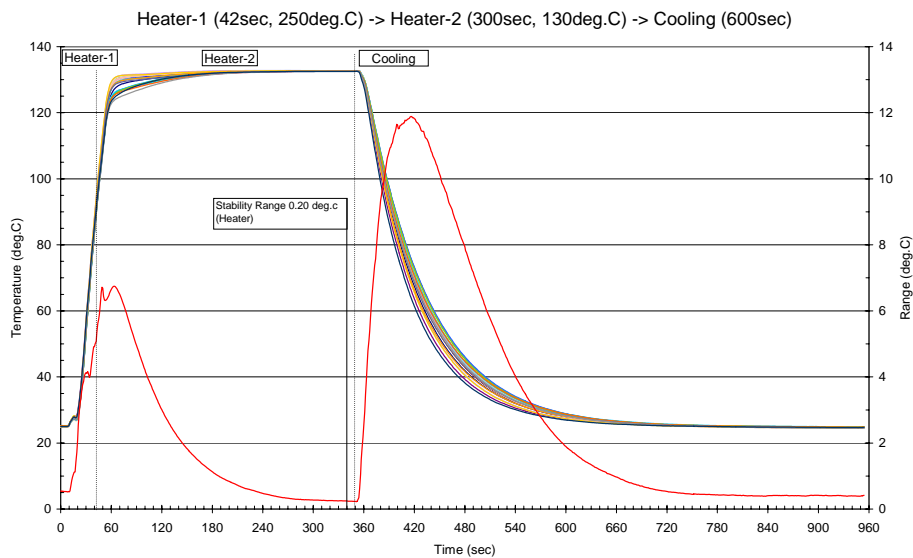


AccuTherm RBS

Fully Automated Rapid Thermal Baking System

Application: Rapid thermal ramp photomask system like silicon wafer's

In Brief: By reducing the ramp time to temperature a significant improvement in contrast performance can be achieved, Rapid thermal ramping of the photomask reduces variations in lateral acid diffusion in the critical 80-120°C temperature range during ramp. Mechanisms contributing to this effect are under review.



Features and Benefits

Feature	Benefit
Rapid Ramp Rate	<ul style="list-style-type: none"> Improves overall contrast performance
Multi-plate Design	<ul style="list-style-type: none"> All masks have same signature Eliminates "matching" of bake modules Increased Throughput
Dynamic Temperature Control	<ul style="list-style-type: none"> Thermal sink capability improves process control by placing constant load on heat array allowing better control/uniformity
Multizone Design	<ul style="list-style-type: none"> Compensate for variations in heating pattern density Increased temperature uniformity Temperature profile capability